

METHOD FOR IMPROVING FILM UNIFORMITY IN PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION SYSTEM

ABSTRACT OF THE DISCLOSURE

A method for improving uniformity of a film in a plasma enhanced chemical vapor deposition system in a deposition chamber includes the following steps before a deposition procedure. Firstly, a cleaning procedure is performed to remove particles adhered onto an internal wall of the deposition chamber. Then, a pre-deposition procedure is performed to isolate contaminants generated during the clearing procedure. Afterward, a specified gas is introduced into the deposition chamber so as to stabilize a condition inside the deposition chamber.